

The NSF IUCRC Center for Microcontamination Control Announces:

The 4th International Surface Cleaning Workshop

<http://www.cmc.neu.edu/surfacecleaning2006>

Call for Papers and Participation

Hosted By:



Co-Sponsored by:



Hanyang University



THE UNIVERSITY OF
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Location and Dates:

Tutorial: November 6, 2006, Northeastern University
Workshop: November 7-8, 2006, Colonnade Hotel, Boston
Reception: November 7, 2006, Northeastern University

Media Sponsor:



“Future and Current Challenges in Surface Cleaning”

A workshop for semiconductor manufacturers, equipment vendors, suppliers and researchers in the field to share and discuss current and future challenges and advances in surface cleaning.

Objective:

To present and discuss current and future challenges and solutions in surface cleaning to the surface cleaning community. The workshop will give end-users, researchers and suppliers a forum to discuss new technologies, solutions and limitations in meeting surface cleaning needs for the year 2006 and beyond. The Conference will include invited and contributed presentations and panel discussions.

Authors are encouraged to include new experimental results and findings in their presentations. Topics include, but are not limited to:

- **New and emerging cleaning technologies**
- **Damage issues during cleaning**
- **Challenges in Single Wafer and EUV Mask cleaning**
- **Post-CMP cleaning challenges and solutions**
- **Physical cleaning techniques (megasonic, brush, laser, etc.)**
- **Surface Cleaning for Cu and low-k and high-K dielectrics**
- **Effect of Chemistry on Cleaning**
- **Issues in cleaning large substrates (300 mm wafers)**
- **Economical (Cost of Ownership) and environmental (EHS) impact of surface cleaning**

Submissions:

Prospective authors are requested to submit an abstract of 200-300 words that includes a summary of significant results and a short biography by **Friday, September 15th, 2006**. Please include presenter's name, title, company, address, telephone, fax and email. Authors selected to present at the symposium will be notified shortly after the above deadline. If your presentation is accepted, a copy of the presentation slides will be included in the workshop web proceedings.

Tutorial:

Fundamental of Surface Cleaning with Emphasis on Post-CMP Cleaning, Ahmed Busnaina
Monday, November 6, 2006 (Full Day)

More Information:

Further information will be posted as the event approaches. If you have any questions, please contact: Jennifer Bose, Finance and Administration, Tel: (617) 373-3294, Fax: (617) 373-2921, j.bose@neu.edu

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